Amendments to the Claims

The listing of claims will replace all prior versions, and listings of claims in the application.

1. (Currently Amended) A method for forming a pattern within an area of a photosensitive surface, comprising:

performing a first exposure of the photosensitive surface in accordance with predetermined image data;

wherein the first exposure produces a first image within the area;
identifying image deficiencies within a region of the first image;
adjusting the image data to compensate for the identified image deficiencies; and
performing a second exposure of the photosensitive surface in accordance with
the adjusted image data;

wherein the step of performing a second exposure includes (i) forming a second image within an object plane including seam thickening and (ii) printing the second image within the area, the printing producing the corrected image in an image plane.

- 2. (Original) The method of claim 1, wherein the image data includes pixel modulation information.
 - 3. (cancelled).
- 4. (Original) The method of claim 1, wherein the identifying step is performed apriorily based upon modeling/simulation.

- 5. (Original) The method of claim 1, wherein the identifying step is performed in real-time based upon image deficiency predictions.
- 6. (Original) The method of claim, 1, wherein the deficiencies include stitching errors.
- 7. (Original) The method of claim 1, wherein the region is a stitching seam separating exposure zones.
 - 8. (cancelled)
- 9. (Original) The method of claim 1, wherein the second exposure step produces a corrected image within the area devoid of the identified image deficiencies.
 - 10. (cancelled)
- 21. (Currently Amended) A computer readable medium carrying one or more sequences of one or more instructions for execution by one or more processors to perform a method of a method of forming a pattern within an area of a photosensitive surface, the instructions when executed by the one or more processors, cause the one or more processors to perform the steps of:

performing a first exposure of the photosensitive surface in accordance with predetermined image data;

wherein the first exposure produces a first image within the area;
identifying image deficiencies within a region of the first image;
adjusting the image data to compensate for the identified image deficiencies; and performing a second exposure of the photosensitive surface in accordance with the adjusted image data:

wherein the step of performing a second exposure includes (i) forming a second image within an object plane including seam thickening and (ii) printing the second image within the area, the printing producing the corrected image within an image plane.

22. (Currently amended) A method for forming a pattern within an area of a photosensitive surface, comprising:

performing a first exposure of the photosensitive surface in accordance with predetermined image data;

wherein the first exposure produces a first image within the area;
adjusting the image data to compensate for image deficiencies; and
performing a second exposure of the photosensitive surface in accordance with
the adjusted image data, the image deficiencies being within a region of the first image;

wherein the step of performing a second exposure includes (i) forming a second image within an object plane including seam thickening and (ii) printing the second image within the area, the printing producing the corrected image within an image plane.